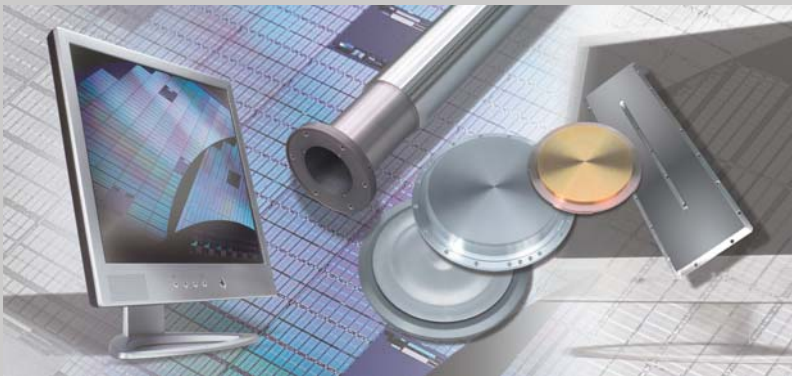


Sputtering Targets for Electronic Applications



Standard Products

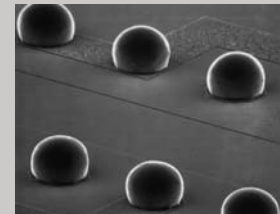
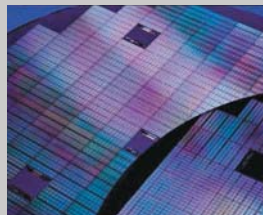
Ag (4N)	Au (4N, 5N)	AuSn (4N)	CuCr (3N5)	Mo (3N5)	NiPt (4N)	Ru (3N)	Ti (3N, 4N5, 5N)
Al (5N, 5N5)	AuAs (4N)	Cr (3N5)	CuNi (3N5)	Ni (3N5)	OsRu (3N5)	Si (5N)	W (3N5)
AlCu (5N, 5N5)	AuGe (4N)	CrNiAl (3N)	GeS ₂ (3N)	NiAl (3N5)	Pd (3N5)	Ta (3N5)	WTi (4N5)
AlSi (5N, 5N5)	AuSb (4N)	CrSi (3N)	Hf (3N)	NiCr (3N5)	Pt (3N5, 4N)	TaAl (3N5)	
AlSiCu (5N, 5N5)	AuSi (4N)	Cu (4N5, 5N)	Ir (3N)	NiV (3N5)	Rh (3N)		

The data given here are correct for March 2006. We reserve the right to make technical alterations as necessary.

Delivery Forms

W. C. Heraeus offers a wide range of sputtering targets and evaporation materials for all major electronics and semiconductor applications:

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